

# Asif Khan

## List of Publications by Year in descending order

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68

papers

1,985

citations

430874

18

h-index

243625

44

g-index

70

all docs

70

docs citations

70

times ranked

2096

citing authors

| #  | ARTICLE  | IF   | CITATIONS |
|----|--|------|-----------|
| 1  | Electron mobility and velocity in Al <sub>0.45</sub> Ga <sub>0.55</sub> N-channel ultra-wide bandgap HEMTs at high temperatures for RF power applications. <i>Applied Physics Letters</i> , 2022, 120, .   | 3.3  | 3         |
| 2  | Small signal analysis of ultra-wide bandgap Al <sub>0.7</sub> Ga <sub>0.3</sub> N channel MESFETs. <i>Microelectronic Engineering</i> , 2021, 237, 111495.   | 2.4  | 2         |
| 3  | High-current recessed gate enhancement-mode ultrawide bandgap Al <sub>x</sub> Ga <sub>1-x</sub> N channel MOSFET with drain current 0.48 A mm <sup>2</sup> and threshold voltage +3.6 V. <i>Applied Physics Express</i> , 2021, 14, 014003.  | 2.4  | 8         |
| 4  | High-Current-Density Enhancement-Mode Ultrawide-Bandgap AlGaN Channel Metal-Insulator-Semiconductor Heterojunction Field-Effect Transistors with a Threshold Voltage of 5 V. <i>Physica Status Solidi - Rapid Research Letters</i> , 2021, 15, 2000576.  | 2.4  | 5         |
| 5  | High In-Plane Thermal Conductivity of Aluminum Nitride Thin Films. <i>ACS Nano</i> , 2021, 15, 9588-9599.  | 14.6 | 58        |
| 6  | Investigation of MOCVD grown crack-free 4 Å thick aluminum nitride using nitrogen as a carrier gas. <i>MRS Advances</i> , 2021, 6, 456-460.  | 0.9  | 5         |
| 7  | Spatially resolved Fourier transform impedance spectroscopy: A technique to rapidly characterize interfaces, applied to a QD/SiC heterojunction. <i>Applied Physics Letters</i> , 2021, 118, 223102.   | 3.3  | 0         |
| 8  | Enhanced light extraction efficiency of micropixel geometry AlGaN DUV light-emitting diodes. <i>Applied Physics Express</i> , 2021, 14, 084002.  | 2.4  | 25        |
| 9  | Thermoreflectance Imaging of (Ultra)wide Band-Gap Devices with MoS <sub>2</sub> Enhancement Coatings. <i>ACS Applied Materials &amp; Interfaces</i> , 2021, 13, 42195-42204.   | 8.0  | 7         |
| 10 | Growth evolution of high-quality MOCVD aluminum nitride using nitrogen as carrier gas on the sapphire substrate. <i>Journal of Materials Research</i> , 2021, 36, 4360-4369.   | 2.6  | 9         |
| 11 | Excimer laser liftoff of AlGaN/GaN HEMTs on thick AlN heat spreaders. <i>Applied Physics Letters</i> , 2021, 119, .  | 3.3  | 5         |
| 12 | All MOCVD grown Al <sub>0.7</sub> Ga <sub>0.3</sub> N/Al <sub>0.5</sub> Ga <sub>0.5</sub> N HFET: An approach to make ohmic contacts to Al-rich AlGaN channel transistors. <i>Solid-State Electronics</i> , 2020, 164, 107696.   | 1.4  | 17        |
| 13 | An Initial Study of Ultraviolet C Optical Losses for Monolithically Integrated AlGaN Heterojunction Optoelectronic Devices. <i>Physica Status Solidi (A) Applications and Materials Science</i> , 2020, 217, 1900801.  | 1.8  | 4         |
| 14 | Temperature characteristics of high-current UWBG enhancement and depletion mode AlGaN-channel MOSFETs. <i>Applied Physics Letters</i> , 2020, 117, 232105.   | 3.3  | 5         |
| 15 | Bulk-like Intrinsic Phonon Thermal Conductivity of Micrometer-Thick AlN Films. <i>ACS Applied Materials &amp; Interfaces</i> , 2020, 12, 29443-29450.  | 8.0  | 22        |
| 16 | Al <sub>0.65</sub> Ga <sub>0.35</sub> N/Al <sub>0.4</sub> Ga <sub>0.6</sub> N Micro-Channel Heterojunction Field Effect Transistors With Current Density Over 900 mA/mm. <i>IEEE Electron Device Letters</i> , 2020, 41, 677-680.  | 3.9  | 19        |
| 17 | High-Temperature Operation of Al <sub>x</sub> Ga <sub>1-x</sub> N (x<0.4) Channel Metal Oxide Semiconductor Heterostructure Field Effect Transistors with High-k Atomic Layer Deposited Gate Oxides. <i>Physica Status Solidi (A) Applications and Materials Science</i> , 2020, 217, 1900802. | 1.8  | 8         |
| 18 | BaTiO <sub>3</sub> /Al <sub>0.58</sub> Ga <sub>0.42</sub> N lateral heterojunction diodes with breakdown field exceeding 8 MV/cm. <i>Applied Physics Letters</i> , 2020, 116, .  | 3.3  | 17        |

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|----|---|-----|-----------|
| 19 | Experimental observation of high intrinsic thermal conductivity of AlN. Physical Review Materials, 2020, 4, .   | 2.4 | 60        |
| 20 | Ultrawide bandgap Al <sub>x</sub> Ga <sub>1-x</sub> N channel heterostructure field transistors with drain currents exceeding 1.3 A mm <sup>2</sup> . Applied Physics Express, 2020, 13, 094002.  | 2.4 | 8         |
| 21 | Design of compositionally graded contact layers for MOCVD grown high Al-content AlGaN transistors. Applied Physics Letters, 2019, 115, .  | 3.3 | 17        |
| 22 | Ultra-wide bandgap AlGaN metal oxide semiconductor heterostructure field effect transistors with high-k ALD ZrO <sub>2</sub> dielectric. Semiconductor Science and Technology, 2019, 34, 125001.  | 2.0 | 12        |
| 23 | Current collapse in high-Al channel AlGaN HFETs. Applied Physics Express, 2019, 12, 074001.   | 2.4 | 11        |
| 24 | Al <sub>0.75</sub> Ga <sub>0.25</sub> N/Al <sub>0.6</sub> Ga <sub>0.4</sub> N heterojunction field effect transistor with f <sub>T</sub> of 40 GHz. Applied Physics Express, 2019, 12, 066502.  | 2.4 | 24        |
| 25 | RF Performance of 130 nm Al <sub>0.75</sub> Ga <sub>0.25</sub> N/Al <sub>0.6</sub> Ga <sub>0.4</sub> N HFETs with MBE-Regrown Contacts. , 2019, , .   |     | 0         |
| 26 | Trap characterization in ultra-wide bandgap Al <sub>0.65</sub> Ga <sub>0.4</sub> N/Al <sub>0.4</sub> Ga <sub>0.6</sub> N MOSFET's with ZrO <sub>2</sub> gate dielectric using optical response and cathodoluminescence. Applied Physics Letters, 2019, 115, 213502. | 3.3 | 3         |
| 27 | Scattering and Quantum Effects in $\text{Al}_{0.65}\text{Ga}_{0.35}\text{N}/\text{Al}_{0.4}\text{Ga}_{0.6}\text{N}$ Heterostructures for High-Power and High-Frequency Electronics. Physical Review Applied, 2018, 9, .   | 3.8 | 14        |
| 28 | All MOCVD grown 250 nm gate length Al <sub>0.70</sub> Ga <sub>0.30</sub> N MESFETs. , 2018, , .   |     | 1         |
| 29 | Ultra-wide band gap materials for high frequency applications. , 2018, , .  |     | 3         |
| 30 | Doped Barrier Al <sub>0.65</sub> Ga <sub>0.35</sub> N/Al <sub>0.40</sub> Ga <sub>0.60</sub> N MOSFET With SiO <sub>2</sub> Gate-Insulator and Zr-Based Ohmic Contacts. IEEE Electron Device Letters, 2018, 39, 1568-1571.   | 3.9 | 33        |
| 31 | High-speed solar-blind UV photodetectors using high-Al content Al <sub>0.64</sub> Ga <sub>0.36</sub> N/Al <sub>0.34</sub> Ga <sub>0.66</sub> N multiple quantum wells. Applied Physics Express, 2017, 10, 011004.   | 2.4 | 20        |
| 32 | Selective area deposited n-AlGaN channel field effect transistors with high solar-blind ultraviolet photo-responsivity. Applied Physics Letters, 2017, 110, .   | 3.3 | 16        |
| 33 | High temperature operation of n-AlGaN channel metal semiconductor field effect transistors on low-defect AlN templates. Applied Physics Letters, 2017, 110, 193501.   | 3.3 | 19        |
| 34 | High Electron Mobility Transistors With Al <sub>0.65</sub> Ga <sub>0.35</sub> N Channel Layers on Thick AlN/Sapphire Templates. IEEE Electron Device Letters, 2017, 38, 914-917.  | 3.9 | 50        |
| 35 | High detectivity visible-blind SiF <sub>4</sub> grown epitaxial graphene/SiC Schottky contact bipolar phototransistor. Applied Physics Letters, 2017, 111, .  | 3.3 | 16        |
| 36 | Al <sub>0.65</sub> Ga <sub>0.35</sub> N channel high electron mobility transistors on AlN/ sapphire templates. , 2017, , .  |     | 1         |

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|----|--|------|-----------|
| 37 | Quasi-pseudomorphic AlGaN based deep ultraviolet LEDs over sapphire substrates., 2015, , .   | 1    |           |
| 38 | Pulsed modulation doping of Al <sub>x</sub> Ga <sub>1-x</sub> N ( $x > 0.6$ ) AlGaN epilayers for deep UV optoelectronic devices. <i>Physica Status Solidi C: Current Topics in Solid State Physics</i> , 2014, 11, 408-411.                           | 0.8  | 1         |
| 39 | Pseudomorphic Al <sub>x</sub> Ga <sub>1-x</sub> N MQW based deep ultraviolet light emitting diodes over sapphire. <i>Physica Status Solidi C: Current Topics in Solid State Physics</i> , 2014, 11, 798-801.   | 0.8  | 7         |
| 40 | Deep ultraviolet photopumped stimulated emission from partially relaxed AlGaN multiple quantum well heterostructures grown on sapphire substrates. <i>Journal of Vacuum Science and Technology B:Nanotechnology and Microelectronics</i> , 2014, 32, . | 1.2  | 12        |
| 41 | Enhancement of light extraction efficiency in sub-300nm nitride thin-film flip-chip light-emitting diodes. <i>Solid-State Electronics</i> , 2013, 89, 156-160.   | 1.4  | 18        |
| 42 | Substrate Lifted-off AlGaN/AlGaN Lateral Conduction Thin-Film Light-Emitting Diodes Operating at 285 nm. <i>Japanese Journal of Applied Physics</i> , 2013, 52, 08JG14.  | 1.5  | 13        |
| 43 | High-Temperature Performance of AlGaN/GaN MOSHEMT With \$hbox{SiO}_2\$ Gate Insulator Fabricated on Si (111) Substrate. <i>IEEE Transactions on Electron Devices</i> , 2012, 59, 2424-2429.  | 3.0  | 72        |
| 44 | A Hybrid Micro-Pixel Based Deep Ultraviolet Light-Emitting Diode Lamp. <i>Applied Physics Express</i> , 2011, 4, 012102.   | 2.4  | 31        |
| 45 | Structural Characterization of Highly Conducting AlGaN ( $x > 50\%$ ) for Deep-Ultraviolet Light-Emitting Diode. <i>Journal of Electronic Materials</i> , 2011, 40, 377-381.   | 2.2  | 17        |
| 46 | Elevated-Temperature Annealing Effects on AlGaN/GaN Heterostructures. <i>Journal of Electronic Materials</i> , 2011, 40, 2344-2347.  | 2.2  | 3         |
| 47 | Dislocation reduction in high Al-content AlGaN films for deep ultraviolet light emitting diodes. <i>Physica Status Solidi (A) Applications and Materials Science</i> , 2011, 208, 1501-1503.   | 1.8  | 8         |
| 48 | High voltage operation of field-plated AlInN HEMTs. <i>Physica Status Solidi C: Current Topics in Solid State Physics</i> , 2011, 8, 2454-2456.  | 0.8  | 15        |
| 49 | 276 nm Substrate-Free Flip-Chip AlGaN Light-Emitting Diodes. <i>Applied Physics Express</i> , 2011, 4, 032102.   | 2.4  | 45        |
| 50 | Ohmic Contact to High-Aluminum-Content AlGaN Epilayers. <i>Journal of Electronic Materials</i> , 2009, 38, 2348-2352.  | 2.2  | 17        |
| 51 | Reliability issues in AlGaN based deep ultraviolet light emitting diodes. <i>Reliability Physics Symposium, 2009 IEEE International</i> , 2009, , .  | 0.0  | 5         |
| 52 | Ultraviolet light-emitting diodes based on group three nitrides. <i>Nature Photonics</i> , 2008, 2, 77-84.   | 31.4 | 891       |
| 53 | RF large-signal model for SiO <sub>2</sub> /AlGaN/GaN MOSFETs. , 2008, , .   | 3    |           |
| 54 | Determination of the channel temperature in GaN MOSFETs under microwave operational conditions. , 2007, , .  | 0    |           |

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|----|---|-----|-----------|
| 55 | Selective doping and optimization of InGaN channel and InGaN backbarrier in deep submicron GaN heterojunction field effect transistor with a recessed gate. , 2007, , .   | 0   |           |
| 56 | Metalâ€“Organic Hydride Vapor Phase Epitaxy of Al <sub>x</sub> Ga <sub>1-x</sub> N Films over Sapphire. Japanese Journal of Applied Physics, 2007, 46, L752-L754.         | 1.5 | 23        |
| 57 | Deep ultraviolet light-emitting diodes. Physica Status Solidi (A) Applications and Materials Science, 2006, 203, 1815-1818.   | 1.8 | 67        |
| 58 | Epitaxial Al/GaN and Au/GaN junctions on as-grown GaN(0001)1 Å– 1 surfaces. Physica Status Solidi (A) Applications and Materials Science, 2005, 202, 804-807.             | 1.8 | 1         |
| 59 | Nanoscale Capacitance-Voltage Characterization of Two-Dimensional Electron Gas in AlGaN/GaN Heterostructures. Japanese Journal of Applied Physics, 2005, 44, L1348-L1351. | 1.5 | 5         |
| 60 | Surface Acoustic Waves And Guided Optical Waves In AlGaN Films. Materials Research Society Symposia Proceedings, 2003, 764, 1.  | 0.1 | 1         |
| 61 | STRAIN ENERGY BAND ENGINEERING APPROACH TO AlN/GaN/InN HETEROJUNCTION DEVICES. International Journal of High Speed Electronics and Systems, 2002, 12, 401-419.            | 0.7 | 2         |
| 62 | AlGaN/InGaN/GaN Double Heterostructure Field-Effect Transistor. Japanese Journal of Applied Physics, 2001, 40, L1142-L1144.   | 1.5 | 111       |
| 63 | Low resistance Ti/Pt/Au ohmic contacts to p-type GaN. Applied Physics Letters, 2000, 76, 3451-3453.   | 3.3 | 79        |
| 64 | Strain energy band engineering approach to AlN/GaN/InN heterojunction devices. , 0, , .   | 0   |           |
| 65 | Subterahertz detection by high electron mobility transistors at large forward gate bias. , 0, , .   | 3   |           |
| 66 | AlGaN/GaN HEMT high-power and low-noise performance at fâ‰¥20 GHz. , 0, , .   | 6   |           |
| 67 | X-ray diffraction imaging of wide bandgap materials. , 0, , .   | 1   |           |
| 68 | Realization of flexible AlGaN/GaN HEMT by laser liftoff. Applied Physics Express, 0, , .  | 2.4 | 0         |